

Smart power technology needs smart substrate

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Soitec product portfolio adapted to wide markets

| | | Applications | | | | | |
|---------------------------------|-------------------------------|--|--------------------|----------------------------------|--------------------------------------|--------------|----------------------|
| | | Digital | Power / analog | RF | Image sensors | Photonics | MEMS |
| M a r k e t s | Computing / Infrastructure | The second s | | | | 00 | |
| | Consumer / Mobility | | | | | | |
| | Automotive and industrial | | | | | | |
| | | | | | | | |
| | Soitec product | FD-2D FD-3D Premium SOI | Smart Power SOI | Wave SOI HRSOI- eSI RF SOS | Imager SOI Stacking for Imager | Photonics SO | Stacking for MEMS |
| | | | | | | | |
| Soite | c | | | | | | |

Soitec – Leader in Engineered Substrates



Outline

- 1. Power market overview
- 2. BCDMOS and isolation technologies
- 3. Smart Cut[™] SOI: a cost competitive technology
- 4. Conclusion

Market BCDMOS SOI Conclusion

Wide range of application & Large market size



Smart power evolution

Logic function (CMOS)

TITT

Smart control Interface to digit

MICROCONTROLLER





Basic power function



NVM Memory

Store state Smart evolution

Control sensor Voltage/current overload Temperature

6

Integration examples



BCDMOS

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BiPolar + CMOS + DMOS = integration of Analog + logic + power functions SMART POWER technology

MarketBCDMOSSOIConclusionIntegration of different voltagesKey process is isolation



PN junction isolation

- -Deep implant
- -Large guard ring
- -Surface penalty

Deep trench isolation and PN junction

-Deep trench for lateral isolation -PN junction for vertical isolation -Reduced surface penalty

Deep trench isolation and SOI

- -Full isolation (lateral and vertical)
- -Surface saving
- -EMI immunity

Bulk low voltage and high voltage integration : Electric isolation through pn-junctions

BCDMOS

Soitec



To isolate low voltage and high voltage areas : Lateral pn-junction Vertical pn-junction (impose a p substrate with n-epi layer)

Deep trench isolation :

BCDMOS

Electric isolation through dielectric trenches and pn-junctions



Parasitic pn junction

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Increase trench isolation breakdown through voltage divider concept Vertical pn-junction (impose a p substrate with n-epi layer)

MarketBCDMOSSOIConclusDielectric isolation benefits :

Silicon island enables different voltage integration

| Low voltage (LDMOS) | High voltage (LIGBT) | | | |
|-------------------------------------|----------------------|-------|--|--|
| Source Gate Drain Source Gate Drain | Source Gate | Drain | | |
| | | _ | | |
| P+ P- wel | P- well | on 7+ | | |
| | | | | |
| | | | | |
| | | | | |
| p-doped substrate | | | | |
| | | | | |

Parasitic pn junction

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Remove parasitic pn-junction Improves leakage performances, thermal range operation

MarketBCDMOSSOIConclusionSOI benefit at the device level

Improvement benefit by categories



ket | BCDN

MOS

Conclusion

Die shrink enables cost effective solution

SOI



Market BCDMOS SOI Conclusion RESURF (Reduces Surface Field) Technology How to guarantee a high Breakdown voltage



Fig.2. Schematic equipotential lines and E-field in bulk and at the surface for various t_{epi} : (a) for 50µm at BV= 370-470V; (b) for 15µm at BV=1150V [after 2,2A].



Relationship between silicon thickness and doping concentration : to guarantee

electrical field in the drift region \leq critical field (limit)

Market BCDMOS SOI Conclu RESURF Technology in SOI Two options Concluster Concluster

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S. HU & AI, Int. Conf. on Communication, Circuits and Systems, ICCCAS 2008

BCDMOS SOI

Conclusion

SOI-BCDMOS flavors: Get more benefit from SOI





Benefit at chip level and system level

SOI



BCDMOS

Conclusion

SOI penetration in power market

SOI



Conclusion

- Power market is going smart 1.
 - Power distribution is going Smart grid
 - Remote control of all power consumption for better global efficiency
- 2. Mix-voltage integration is key
 - Integrate different voltage requirements for remote control, logic, sensor, power conversion
 - Enable power efficiency (conversion and usage)
- 3. SOI provides better performances and smaller die

 - Simplify design cycle for time to market High temperature and truly latch-up free operation Thin SOI-BCDMOS design brings additional benefits (switching speed, low Rdson)
- 4. SOI for smart power is cost effective
 - Substrate performance impacts on chip design, size and cost
 - Optimized SOI design per application enable high competitive solution



Thank you for your attention